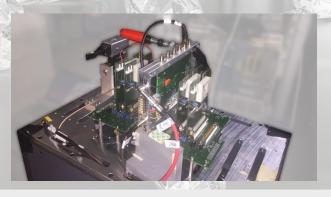


Eidgenössische Technische Hochschule Zürich Swiss Federal Institute of Technology Zurich





Single and Double Channel Measurements of the BCM' at PSI

RD42 Meeting, Ljubljana

#### Michael Reichmann

8th November 2018

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# Section 1

### Introduction

#### Introduction

- after troubles at CERN also measured BCM' at PSI
  - ▶ high particle rate
  - much lower spatial resolution of the telescope
- measured two diamonds with different readout boxes:

	??	II6-H8
manufacturer	II-VI Inc.	II-VI Inc.
diamond type	poly-crystal	poly-crystal
size	$\sim$ 4 mm $ imes$ 4 mm	$\sim$ 4 mm $ imes$ 4 mm
thickness	$\sim$ 500 $\mu$ m	$\sim$ 500 $\mu$ m
amplifier	new OSU fast Amp	new OSU fast Amp
readout box	1	2

- maximum 1 out of 4 amplifier channels per chip can be read out at once
- box 1: original box that blew up the electronics at CERN
  - ▶ internal IV distribution
  - ▶ maximum HV of 300 V
- box 2: different casing with all LV components of box 1 but different HV connector

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#### Measurements

- avoid noise from programming pc:
- lock programming into the amps before every change of channel or chip configuration
  - ► connect 500 mV supply voltage
  - hook up DB connector to the readout boxes
  - ▶ program chip
  - ▶ disconnect DB
  - ground supply voltage line
- every data run is preceded by a pumping run at high rate of the same duration

Box	Chip	Channel	Bias [V]	Events [M]
1	1	1	$\pm 200$	0.8
1	1	1	$\pm 300$	0.8
1	2	1	$\pm 200$	8.0
1	2	1	$\pm 300$	8.0
1	1 & 2	1	$\pm 200$	0.8
2	1 & 2	1	±500	1.6
2	1 & 2	1	$\pm 1000$	1.6

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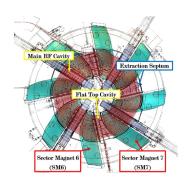
Section 2

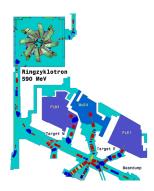
**Test Site** 

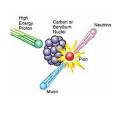


#### Test Site

- High Intensity Proton Accelerator (HIPA) at PSI → beam line PiM1
- clean positive pion beam ( $\sim$ 98 %  $\pi^+$ ) with momentum of 260 MeV/c • 75 % of the signal size at CERN! (120 GeV/c)
- ullet significant multiple scattering o worsens resolution







Section 3

Results

- all pads/channels of the two amplifier chips are connected to the same HV line
- pumping at higher rate induces leakage current in the sensor

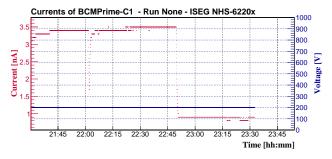


Figure: Box 1 at  $+200 \,\mathrm{V}$ 

stable behaviour at +200 V

- all pads/channels of the two amplifier chips are connected to the same HV line
- pumping at higher rate induces leakage current in the sensor

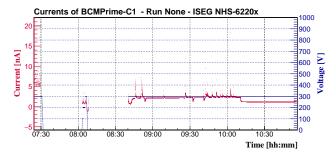


Figure: Box 1 at  $+300\,\mathrm{V}$ 

- stable behaviour at +200 V
- erratic currents up to  $\mathcal{O}(2\,\mu\text{A})$  at high rates at  $+300\,\text{V}$

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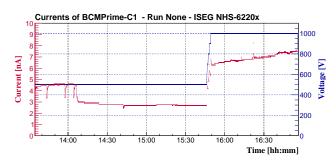


Figure: Box 2 at positive voltage

- ullet very stable behaviour up to  $\pm 1\,\mathrm{kV}$
- ullet slight increase at  $+1\,\mathrm{kV}$

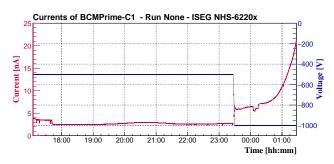


Figure: Box 2 at negative voltage

- $\bullet$  very stable behaviour up to  $\pm 1\,\mathrm{kV}$
- slight increase at +1 kV
- $\bullet$  exponential increase at  $-1 \, kV$

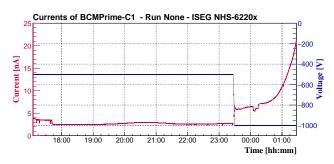


Figure: Box 2 at negative voltage

- ullet very stable behaviour up to  $\pm 1\,\mathrm{kV}$
- ullet slight increase at  $+1\,\mathrm{kV}$
- $\bullet$  exponential increase at  $-1\,\text{kV}$
- current positive independed of bias ...

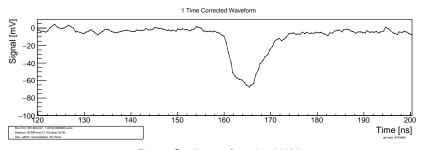


Figure: Single waveform 0 +200 V

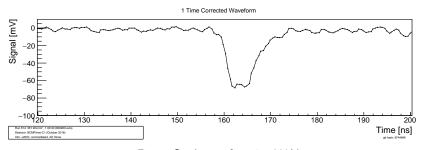


Figure: Single waveform 1 +200 V

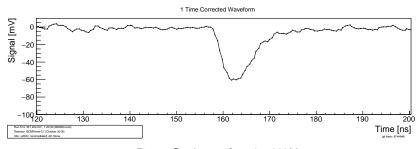


Figure: Single waveform 2 +200 V

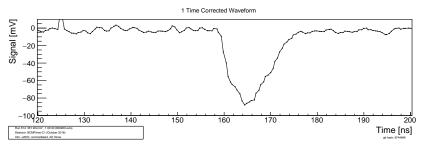


Figure: Single waveform 3 +200 V

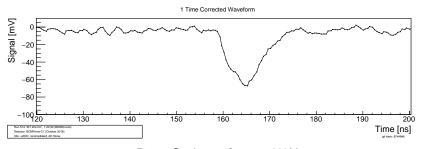


Figure: Single waveform 4 +200 V

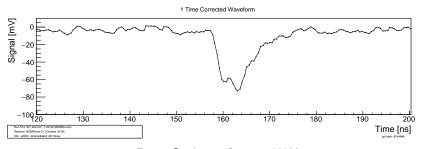


Figure: Single waveform 5 +200 V

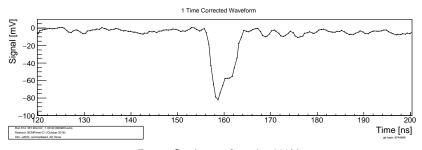


Figure: Single waveform 6 +200 V

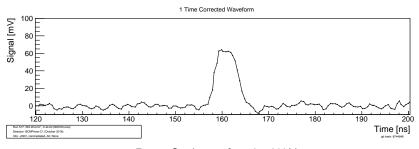


Figure: Single waveform 0 −200 V

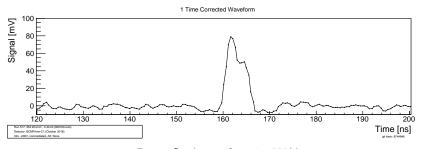


Figure: Single waveform 1 −200 V

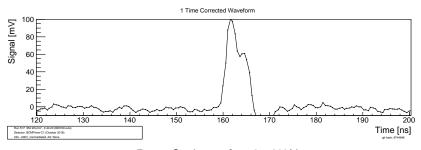


Figure: Single waveform  $2-200\,\mathrm{V}$ 

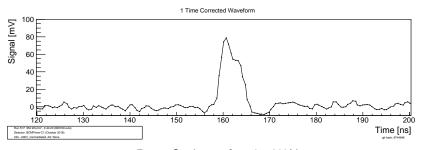


Figure: Single waveform 3 −200 V

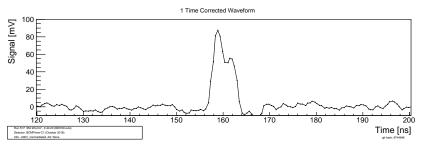


Figure: Single waveform 4  $-200\,\mathrm{V}$ 

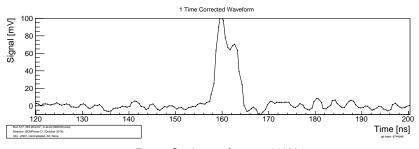
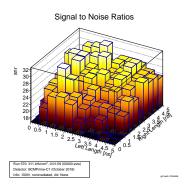


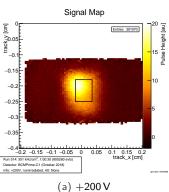
Figure: Single waveform 5 −200 V

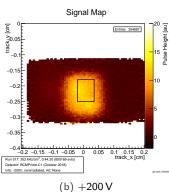
# Waveform Integration / SNR



- choosing the integration width around the peak of the pulse
- chosen values: 1.5 ns before and 3 ns after the pulse

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(a) +200 V

test

# Section 4

# Conclusion

#### Conclusion

- successfully measured two BCM' modules at PSI
- only channel 1 of each chip working at low noise
- possible to read out two channels of independent chips at the same time
- SNR at 1kV:
- shape of negative signals becomes flat before reaching the highest point
- rise time at positive voltage:
- coupling between connected and non-connected channels

